

EXAMINER <i>Walter Anderson</i>	DATE CONSIDERED <i>9/11/02</i>
<p>*EXAMINER: INITIAL IF CITATION CONSIDERED, WHETHER OR NOT CITATION IS IN CONFORMANCE WITH MPEP 609; DRAW LINE THROUGH CITATION IF NOT IN CONFORMANCE AND NOT CONSIDERED, INCLUDE COPY OF THIS FORM WITH NEXT COMMUNICATION TO APPLICANT.</p>	

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FORM PTO-1449	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO. SEPP9.001APC	APPLICATION NO. 09/787,062
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (USE SEVERAL SHEETS IF NECESSARY)		APPLICANT Leskela et al.	
		FILING DATE March 12, 2001	GROUP Unknown

EXAMINER INITIAL	OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)	
<i>NMA</i>	7	Niinistö et al., "Synthesis of oxide thin films and overlayers by atomic layer epitaxy for advanced applications," <u>Materials Science & Engineering</u> , Vol. B41, pp. 23-29 (1996).
<i>NMA</i>	8	Ritala et al., "Growth of titanium dioxide thin films by atomic layer epitaxy," <u>Thin Solid Films</u> , Vol. 225, pp. 288-295 (1993).
<i>NMA</i>	9	Ritala et al., "Titanium Isopropoxide as a Precursor in Atomic Layer Epitaxy of Titanium Dioxide Thin Films," <u>Chem. Mater.</u> , Vol. 5, pp. 1174-1181 (1993).
<i>NMA</i>	10	Ritala et al., "Atomic Layer Epitaxy Growth of Titanium Dioxide Thin Films from Titanium Ethoxide," <u>Chem. Mater.</u> , Vol. 6, pp. 556-561 (1994).
<i>NMA</i>	11	Schulz et al., "MOCVD Routes to Thin Metal Oxide Films for Superconducting Electronics," <u>Adv. Mater.</u> , Vol. 6, No. 10, pp. 719-730 (1994).
<i>NMA</i>	12	Sheppard, "Advances in Processing of Ferroelectric Thin Films," <u>Ceramic Bulletin</u> , Vol. 71, No. 1, (1992).
<i>NMA</i>	13	<u>Advances in Organometallic Chemistry</u> , Ed. Stone and West, Vol. 40, Academic Press (1996).
<i>NMA</i>	14	Suntola, "Atomic layer epitaxy," <u>Thin Solid Films</u> , Vol. 216, pp. 84-89 (1992).
<i>NMA</i>	15	Wojtczak et al., "A Review of Group 2 (Ca, Sr, Ba) Metal-Organic Compounds as Precursors for Chemical Vapor Deposition," <u>Advances in Organometallic Chemistry</u> , Vol. 40, pp. 215-340 Academic Press (1996).

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